Local Alignment of the BaBar Silicon Vertex Tracking Detector

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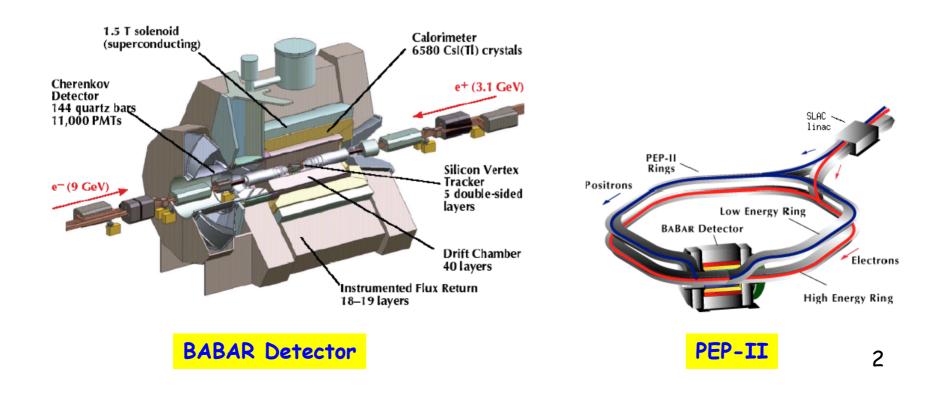
DPF 2009, Wayne State University, Detroit, MI July 31, 2009





The BaBar Experiment

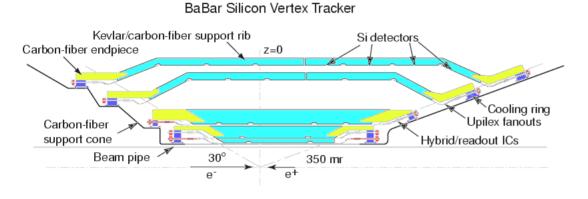
- Silicon Vertex Tracker (SVT): 5 layers of double-sided Si
- Drift chamber (DCH): P measurement and particle ID through dE/dX (low P)
- Detector of Internally Reflected Cherenkov Light (DIRC): particle ID (high P)
- Electromagnetic calorimeter (EMC): π^0 and K⁰-long reconstruction, e ID
- * Instrumented Flux Return (IFR): $\mu\,$ ID and K^o-long reconstruction
- Trigger: Two levels: L1 up to 2 KHz, L3 up to 100 Hz
- Offline software and event store: C++ and Object Oriented databases

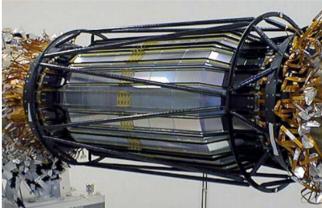












- 340 double-sided Si wafers ~1m² Si
- 5 layers independent tracker
- Unique 'arch' in outer layer inner three layers planar
- CF support structure
- 4% X₀ total
- ~90% of Ω
- Mounted on the innermost magnets

la	ıyer	wafers in module	modules in layer	radius (mm)	z (L) (mm)	φ (W) (mm)
	1	4	6	32	42	41
	2	4	6	40	45	49
	3	6	6	54	44	71
	4	7	16	91 - 127	54-68	43-53
	5	8	18	114–144	68	43-53



Parameterizing the SVT Local Alignment



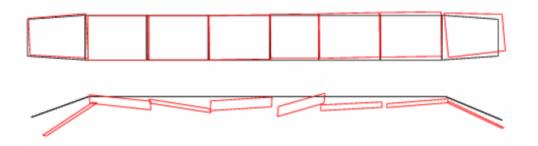
- Determine precise relative position of silicon sensors:
 6 parameters for each of 340 SVT wafers
 3 translations and 3 rotations
- Complex process: - calculate hit residuals, minimize $\chi^{2} \equiv \sum_{i}^{\text{hits}} \epsilon_{i}^{T}(\Delta \mathbf{p}) \mathbf{V}_{i}^{-1} \epsilon_{i}(\Delta \mathbf{p})$ $\underbrace{\mathbf{W}(\mathbf{r})}_{\mathbf{i}} \mathbf{V}(\mathbf{Z})$ $\underbrace{\mathbf{V}(\mathbf{Z})}_{\mathbf{u}(\mathbf{\Phi})}$



Optical Survey Constraint in SVT-LA



We use optical survey information in module plane:



- Important addition to track residual information
- Compute wafer residuals with respect to survey
- χ^2 in module plane (u, v, \mathcal{R}_w) weight 1.0 **5**μ**m** in out-of-module plane: $(w, \mathcal{R}_{u}, \mathcal{R}_{v})$ weight 0.1 20µm

- (1) Constrain wafers within modules
- (2) Constrain dead readout (Z or/and ϕ) wafers







 Determine the local alignment parameters with sufficient accuracy

average resolution: 10µm for u hits and 20µm for γ hits statistical precision and control the systematic errors

- Track-based and lab-bench measurements only constrain the relative positions of nearby wafers raise the risk of introducing a 'global distortion'
- Following the time-dependence of the actual changes in the detector
- Quickly detect when the local alignment changes

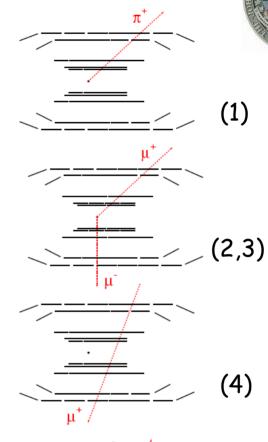


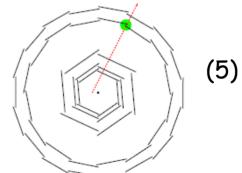
Track/Hit Selection for SVT-LA

- Define five categories

 (1) "normal"
 (2) μ⁺μ⁻
 (3) e⁺e⁻
 (4) cosmic
 (5) overlap hits
 - Sequence
 - dedicated stream/skim/tag
 - apply cuts, tag events/track/hit
 - distribute uniformly over SVT,
 and Z readout, categories
- Select ~ 50,000 tracks
 tag ~ 3-4 hits/track (out of 9-10)

DCH-only fit ω constraint (inverse curvature) greatly improve the momentum resolution of the constrained SVT-only track

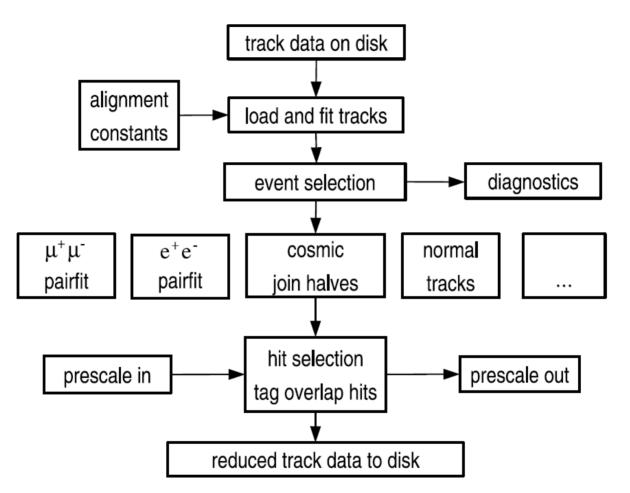






Track/Hit Selection for SVT-LA





Sequence for the event, track, and hit selection, including calculation of prescale factors



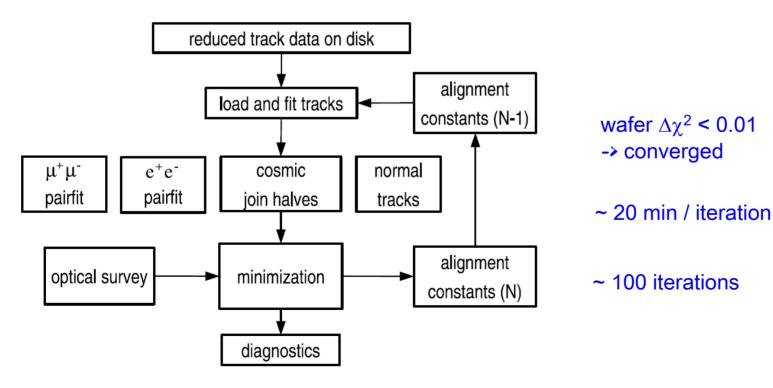
Local Alignment Minimization Procedure



Minimize 340 separate wafer χ^2 independently

$$\chi^2 \equiv \sum_{i}^{\text{hits}} \epsilon_i^T (\Delta \mathbf{p}) \mathbf{V}_i^{-1} \epsilon_i (\Delta \mathbf{p}) + \epsilon_s^T (\Delta \mathbf{p}) \mathbf{V}_s^{-1} \epsilon_s (\Delta \mathbf{p})$$

hit residuals survey residuals

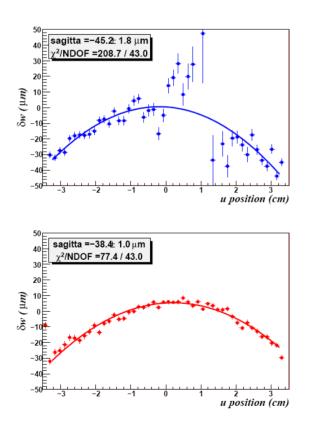




Wafer Curvature



- Radial position is measured by overlaps
 - overlap hits constrain circumference
 - assume flat wafer geometry



u and v hit residuals from high momentum tracks

- non-linear dependence indicates an aplanar wafer distortion, not described by the standard six local alignment parameters
- wafer bowed in the uw plane simple bowing may not be the only aplanar distortion present
- systematic bias on the transverse impact parameter



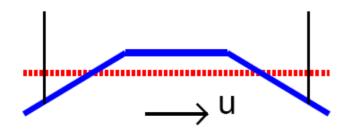
Wafer Curvature

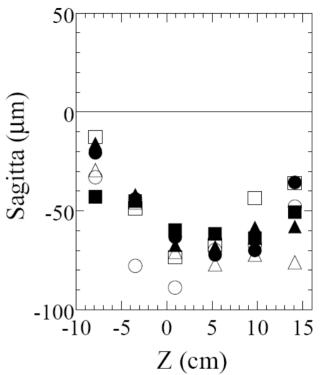


The aplanar wafer distortions must be measured and corrected for the alignment procedure

Wafer bowing in
 model by polygon for Z strips

$$\delta w(u) = (u^2 - u_0^2)/2R$$



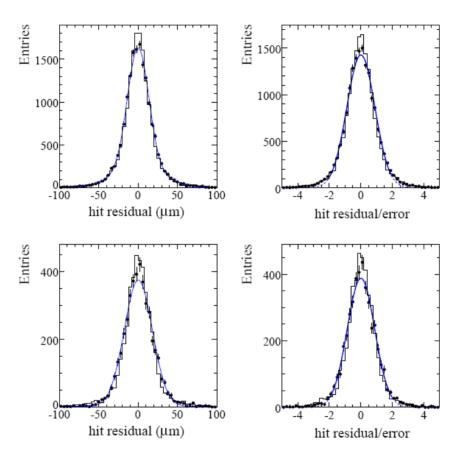


Measure the curvature radius R for each inner-layer wafer by fitting the average u and v residuals dependence on u

adding 84 more parameters

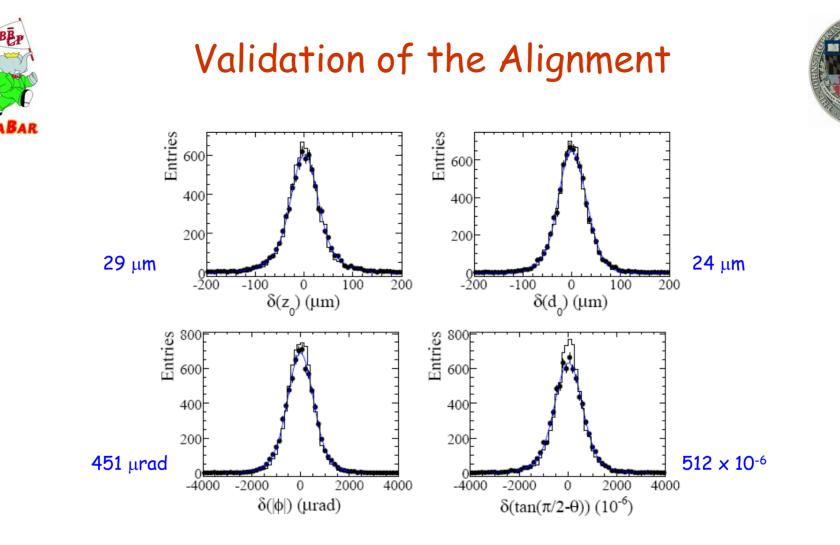


Validation of the Alignment



- Basic test of alignment self-consistency: hit residuals
 - Inner three layers using $e^+e^- \twoheadrightarrow \mu^+\mu^-$
 - 14 (13) μ m for data (MC) u hits, 18 (16) for v hits
 - Good agreement between data and MC

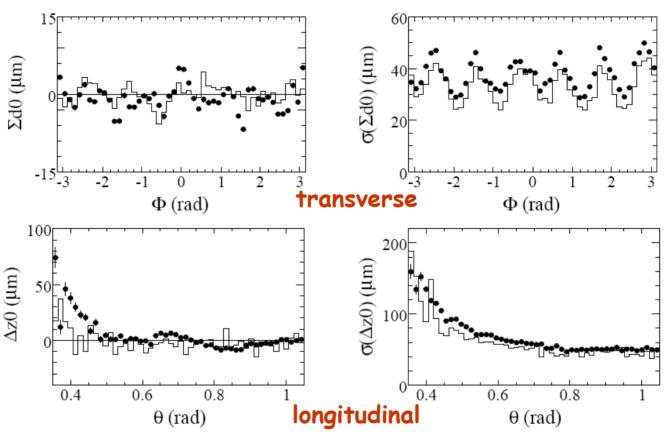




- High-level self-consistency test: cosmic ray splitting
 - incoming and outgoing branches as two separate tracks
 - fit using SVT hits plus a DCH curvature constraint

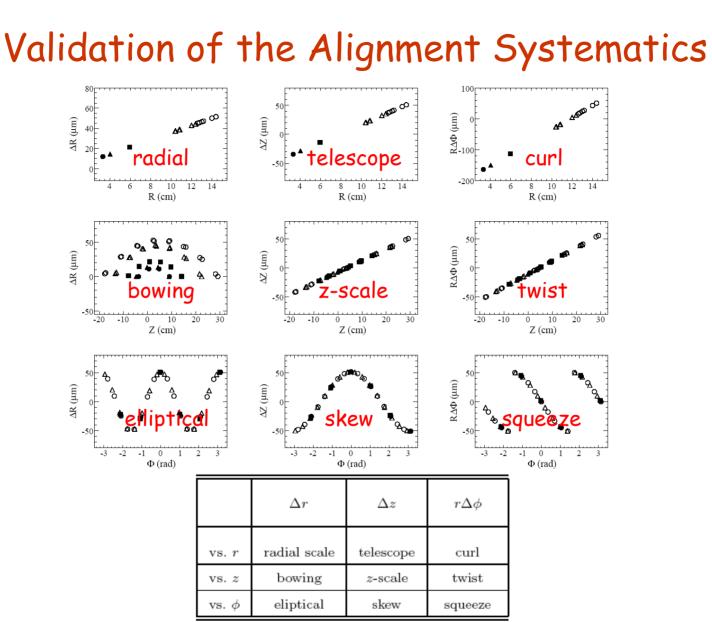


Validation of the Alignment



- Comparing the reconstructed origin points of the two tracks produced in e^e^ -> $\mu^+\mu^-$
 - measure the impact parameter resolution
 - look for systematic biases left by the alignment





Nine distinct distorted initial conditions Set the initial scale to $50 \mu m$







Validation of the Alignment Systematics

20

40

60

Iteration

80

100

0



80

100

curl

Iteration

elliptical

Iteration

60

40

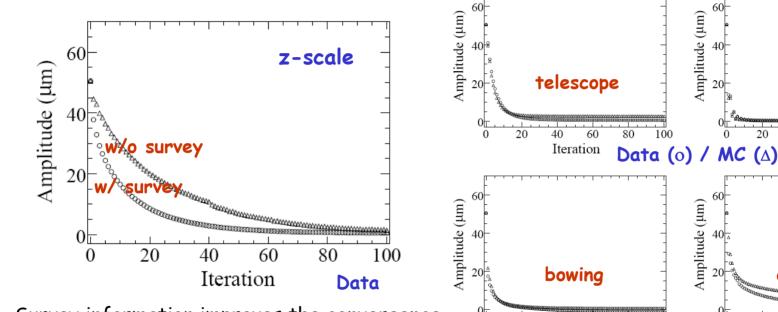
60

40

20

20

0



Survey information improves the convergence and reduce the systematic error

> LA procedure capable of reducing global distortions to a negligible level

Amplitude (µm)

Amplitude (µm)

80

100



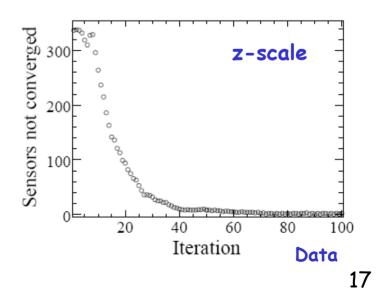
Validation of the Alignment Systematics



	Δr	Δz	$r\Delta\phi$
vs. r	radial	telescope	curl
decay (iterations)	5.6	5.1	1.3
distortion (μm)	0.7	0.5	0.1
vs. z	bowing	z-scale	twist
decay (iterations)	2.6	11.2	12.0
distortion (μ m)	0.6	0.6	0.1
vs. ϕ	eliptical	skew	squeeze
decay (iterations)	11.8	33.6	32.0
distortion (μ m)	0.9	4.9	4.5

Decay time and remaining distortion

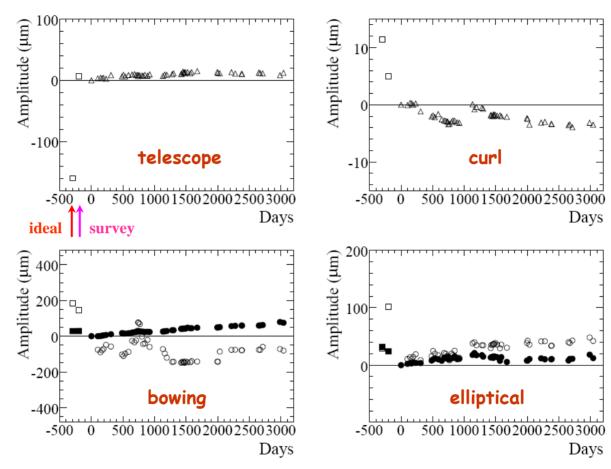
- Global distortions are the most weakly constrained deformations
- The order of 100 iterations necessary to solve for these deformations
- Convergence requirement chosen empirically to allow convergence of the global distortions



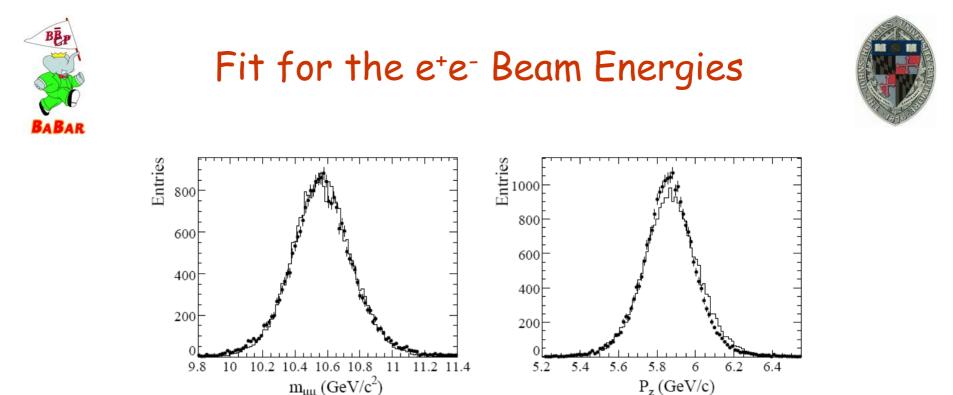
Validation of the Alignment Systematics

BEP





- Time-dependence of global distortion, compared to the initial day-one alignment
 Nov 1999 Apr 2008 data
- Study of potential distortions places limits on systematic uncertainties in physics measurements



- Fit the average $\mu^+\mu^-$ boost and use it in the four-momentum pair constraint instead of the initial state boost
- Iterate, allowing a simultaneous extraction of the boost value and the geometrical constraints
 - makes the local alignment algorithm more stable
 - allow for monitoring the $e^{\scriptscriptstyle +}e^{\scriptscriptstyle -}$ beam boost





Conclusions

- Described the procedure used to determine BaBar SVT local alignment relative positions and orientations of the 340 wafers
- Satisfies the requirements placed on the SVT performance by the BaBar physics goals
- Robust against global distortions